

ISO 14701:2018 (E)

Surface chemical analysis — X-ray photoelectron spectroscopy — Measurement of silicon oxide thickness

Contents

	Foreword
	Introduction
1	Scope
2	Normative references
3	Terms and definitions
4	Abbreviated terms and symbols
4.1	Abbreviated terms
4.2	Symbols
5	Outline of method
6	Method for measuring the oxide thickness
6.1	Cleaning and preparing the sample
6.2	Mounting the sample
6.3	Choosing spectrometer settings
6.4	Recording data
6.5	Measuring intensities
6.6	Calculating the oxide thickness
6.7	Calculating the uncertainty of the oxide thickness

Page count: 17